

Applicants respectfully thank the Examiner for the courtesies extended during the Examiner interview of December 13, 1999.

In the Office Action dated July 20, 1999, the Examiner rejected claims 5, 10 and 13-15 under 35 U.S.C. § 112, second paragraph, rejected claim 1 under 35 U.S.C. § 102(b) as being anticipated by Nelson, rejected claim 2 under 35 U.S.C. § 103(a) as being unpatentable over Nelson in view of Tittle, and rejected claims 3-18 under 35 U.S.C. § 103(a) as being unpatentable over Nelson in view of Jones et al., Tittle and Salzle.

By this Amendment, Applicants amend claims 1, 2, 5, 9-11 and 13-15 and add new claims 19 and 20. Accordingly, claims 1-20 are pending in this application. Applicants have amended the claims to more clearly recite the subject matter of the present invention and respectfully submit that the claims as amended are in full compliance with 35 U.S.C. § 112. Reexamination and reconsideration of the application, as amended, are respectfully requested.

Applicants respectfully traverse the rejections of the claims under 35 U.S.C. §§ 102(b) and 103(a), insofar as they apply to the present claims, and reconsideration is requested.

Claims 1-9 and 11-19 are allowable over the cited references in that these claims recite, in varying degrees of specificity, a combination of features including an etching apparatus for etching a glass substrate comprising an etch bath having a bubble plate, the etch bath being connected to the first tank and receiving the first etchant, the etch bath containing a residual etchant including a diluted etchant and residue material after the glass substrate is etched with the first etchant to reduce a thickness of the glass substrate. None of the cited references, singly or combined, teaches or suggests at least this feature of the present invention.

Claims 10 and 20 are allowable over the cited references in that these claims recite a combination of features including an etching apparatus for etching a glass substrate with an etchant having a control unit for receiving a signal indicating the temperature of the etchant from

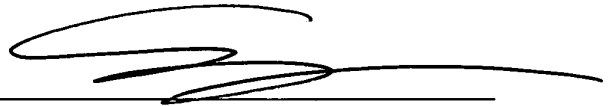
the temperature sensor and transmitting an etching termination signal to the etch bath when the temperature reaches a target temperature. None of the cited references, singly or combined, teaches or suggests at least this feature of the present invention.

Applicants believe the foregoing amendments place the application in condition for allowance and early, favorable action is respectfully solicited.

If for any reason the Examiner finds the application other than in condition for allowance, the Examiner is requested to call the undersigned attorney at the Washington, D.C. telephone number (202) 624-1250 to discuss the steps necessary for placing the application in condition for allowance. All correspondence should continue to be sent to the below-listed address.

Respectfully submitted,

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